IN THE CLAIMS

1. (currently amended): A method of fabricating a protective film comprising:

providing a vacuum ultraviolet radiation CVD (Chemical Vapor Deposition) system comprising a vacuum ultraviolet rays generator, a reactor provided with a platform for supporting a substrate, a heat retainer provided on the platform, and a window separating the vacuum ultraviolet rays generator from the reactor;

feeding an organic stock gas from a gas feeder into the reactor while retaining temperature of the substrate at a [[low]] temperature about equal to or less than 100 °C with the heat retainer; and

irradiating simultaneously the reactor with vacuum ultraviolet rays from the vacuum ultraviolet rays generator through the window.

2. (currently amended): A method of fabricating a protective film according to claim 1, wherein retaining of the temperature with the heat retainer is carried out such that the temperature of the substrate is kept at a low temperature in a range of ~~25 ?C to 100 ?C~~ about 25 °C to 100 °C.

3. (original): The method of fabricating a protective film according to claim 1, wherein an organosilazane gas having Si-N bonds is used for the organic stock gas.

4. (original): The method of fabricating a protective film according to claim 1, further comprising adding an additive gas for increasing nitrogen content in the protective film, or a regulator gas for use in regulating a partial pressure of the organic stock gas in the reactor to the organic stock gas so as to be fed from the gas feeder into the reactor.

5. (new): The method of fabricating a protective film according to claim 1, wherein the vacuum ultraviolet rays photons have energy of about 7.2 eV and wavelength of about 172 nm.

6. (new): The method of fabricating a protective film according to claim 5, wherein the step of providing the ultraviolet rays generator includes providing a xenon excimer lamp.